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Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L3	63	((wafer or semiconductor or substrate) near15 steam\$8) and (liquid or water or solution or fluid chemical or formulation or solvent or surfactant) and ozon\$8 and "134"/\$.ccls.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/11 03:57
L4	71	((wafer or semiconductor or substrate) near15 (rotate or rotated or rotating spun or spinning or spin or rotor or centrifug\$8)) and (liquid or water or solution or fluid chemical or formulation or solvent or surfactant) and steam and ozon\$8 and "134"/\$.ccls.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/11 03:57
S21	350	((wafer or semiconductor or substrate) near15 (rotate or rotated or rotating spun or spinning or spin or rotor or centrifug\$8)) same (liquid or water or solution or fluid) same ((chamber or vessel or processor or housing or enclosure) near5 (heat or heated or heater or heating))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/11 01:36
S23	722	((wafer or semiconductor or substrate) near15 (rotate or rotated or rotating spun or spinning or spin or rotor or centrifug\$8)) and (liquid or water or solution or fluid chemical or formulation or solvent or surfactant) and ((chamber or vessel or processor or housing or enclosure) near5 (heat or heated or heater or heating)) and ozon\$8	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/11 01:41
S25	142	((wafer or semiconductor or substrate) near15 (rotate or rotated or rotating spun or spinning or spin or rotor or centrifug\$8)) and (liquid or water or solution or fluid chemical or formulation or solvent or surfactant) and ((chamber or vessel or processor or housing or enclosure) near5 (heat or heated or heater or heating)) and ozon\$8 and "134"/\$.ccls.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/11 02:22
S37	320	((wafer or semiconductor or substrate) near15 (rotate or rotated or rotating spun or spinning or spin or rotor or centrifug\$8) near15 (inverted or bottom or back or backside)) and (liquid or water or solution or fluid chemical or formulation or solvent or surfactant) and ozon\$8	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/11 02:42

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Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L2	350	((wafer or semiconductor or substrate) near15 (rotate or rotated or rotating spun or spinning or spin or rotor or centrifug\$8)) same (liquid or water or solution or fluid) same ((chamber or vessel or processor or housing or enclosure) near5 (heat or heated or heater or heating))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/11 01:36
L4	722	((wafer or semiconductor or substrate) near15 (rotate or rotated or rotating spun or spinning or spin or rotor or centrifug\$8)) and (liquid or water or solution or fluid chemical or formulation or solvent or surfactant) and ((chamber or vessel or processor or housing or enclosure) near5 (heat or heated or heater or heating)) and ozon\$8	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/11 01:41
L6	142	((wafer or semiconductor or substrate) near15 (rotate or rotated or rotating spun or spinning or spin or rotor or centrifug\$8)) and (liquid or water or solution or fluid chemical or formulation or solvent or surfactant) and ((chamber or vessel or processor or housing or enclosure) near5 (heat or heated or heater or heating)) and ozon\$8 and "134"/\$.ccls.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/11 02:22
L18	320	((wafer or semiconductor or substrate) near15 (rotate or rotated or rotating spun or spinning or spin or rotor or centrifug\$8) near15 (inverted or bottom or back or backside)) and (liquid or water or solution or fluid chemical or formulation or solvent or surfactant) and ozon\$8	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/11 02:30
S13	2108	((lead near2 angle) or (phase near2 lead)) near15 voltage)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/11 00:19

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S39	253	((wafer or semiconductor or substrate) near15 (clean\$8 or wash or washing or decontaminat\$8)) near15 ((inverted or bottom or back or backside underneath or beneath or bottomside) near20 (liquid or water or solution or fluid chemical or formulation or solvent or surfactant)) and ozon\$8	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/11 02:52
S45	341	((wafer or semiconductor or substrate) near15 (rotate or rotated or rotating spun or spinning or spin or rotor or centrifug\$8)) and ((liquid or water or solution or fluid chemical or formulation or solvent or surfactant) near5 ozon\$8) and "134"/\$.ccls:	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/11 03:16
S49	166	((wafer or semiconductor or substrate) near15 (rotate or rotated or rotating spun or spinning or spin or rotor or centrifug\$8)) and ((liquid or water or solution or fluid chemical or formulation or solvent or surfactant) near15 steam) and ozon\$8	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/11 03:29